

STIC Search Report

STIC Database Tracking Number: 174065

TO: Mulero Luz L Alejandro

Location: REM 7A19

Art Unit: 1763

December 13, 2005

Case Serial Number: 10/786914

From: Mrs. Kendra Banks

Location: EIC 1700

REM 4B28

Phone: 571-272-2516

Kendra.Mellerson@uspto.gov

Search Notes

No Cases Reported

US 6,349,670



Mellerson, Kendra

From:

Alejandro, Luz

Sent:

Tuesday, December 13, 2005 10:11 AM

To:

STIC-EIC1700

Subject:

RE: Litigation search for application 10/786914

US 6,349,670

----Original Message-----From:

STIC-EIC1700

Sent:

Tuesday, December 13, 2005 10:05 AM

To:

Alejandro, Luz

Subject:

RE: Litigation search for application 10/786914

Please provide the US patent number.

Thank you,

Kendra

----Original Message----

From:

Alejandro, Luz

Sent:

Tuesday, December 13, 2005 9:59 AM

To:

STIC-EIC1700

Subject:

Litigation search for application 10/786914

Good morning, I need a litigation search for US application 10/786914.

Thank you, Luz Alejandro Art Unit 1763

PATNO IS 6349670

DATE: DECEMBER 13, 2005 LIBRARY: PATENT FILE: ALL

y.

Your search request is: PATNO IS 6349670

Number of PATENTS found with your search request through:

Your search request has found 1 PATENT through Level 1. To DISPLAY this PATENT press either the KWIC, FULL, CITE or SEGMTS key. To MODIFY your search request, press the M key (for MODFY) and then the ENTER key.

For further explanation, press the H key (for HELP) and then the ENTER key.

LEVEL 1 - 1 PATENT

1. 6349670 , February 26, 2002 , Plasma treatment equipment, Nakano, Akira - Miyagi-ken, Japan (JP); Fukuda, Koichi - Miyagi-ken, Japan (JP); Kim, Sung Chul - Kyongki-Do, Japan (JP); Kasama, Yasuhiko - Miyagi-ken, Japan (JP); Ohmi, Tadahiro - Miyagi-ken, Japan (JP); Ono, Shoichi - Miyagi-ken, Japan (JP), 442539 (09), Alps Electric Co., Ltd., Tokyo, Japan (JP), 03, November 18, 1999 - ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS)., ALPS ELECTRIC CO., LTD. 1-7 YUKIGAYA, OTSUKA-CHO OTA-KU, TOKYO JAPAN, Reel and Frame Number: 10399/0481 May 19, 2004 - CORRECTIVE ASSIGNMENT, ALPS ELECTRIC CO., LTD. 1-7 YUKIGAYA, OTSUKA-CHO OTA-KU, TOKYO JAPAN; OHMI, TADAHIRO 2-1-17 KOMEGAFUKURO, AOBA- KU, SENDAI-SHI MIYAGI-KEN JAPAN, Reel and Frame Number: 14635/0321

CORE TERMS: plasma, impedance, chamber, electrode, measured, high frequency, suscepter, measurement, wire, consumption ...

LEVEL 1 - 1 OF 1 PATENT

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

6349670

February 26, 2002

Plasma treatment equipment

REISSUE: February 25, 2004 - Reissue Application filed Ex. Gp.: 1763; Re. S.N. 10/786,914 (O.G. June 1, 2004)

CERT-CORRECTION: September 24, 2002 - a Certificate of Correction was issued for this patent (O.G. October 15, 2002)

APPL-NO: 442539 (09)

FILED-DATE: November 18, 1999

GRANTED-DATE: February 26, 2002

CORE TERMS: plasma, impedance, chamber, electrode, measured, high frequency,

suscepter, measurement, wire, consumption ...

Your search request has found no CASES.

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What you enter will be Search Level 1.

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Patent Search - Number: 6349670

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Current session 13/12/2005

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Last connection: 13/12/05 16*55*44

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- FAMPAT worldwide family file available. Details on website
- PatentExaminer enhancement: integration of FamPat database
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Query/Command: FILE PLUSPAT

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Individual records for each Country or Patent Office

Coverage: 75 patenting authorities; start dates vary from 1800 forward For PlusPat Fact Sheet, Pricing and FAQ, see the Questel.Orbit website Now available: Citations / Search Reports for German (DE) documents Last update of file: 2005/12/07 (YYYY/MM/DD) 2005-48/UP (last update)

Search statement 1

Query/Command: US6349670/PN

** SS 1: Results 1

Search statement 2

Query/Command: PRT FULL NONSTOP LEGALALL

1/1 PLUSPAT - ©QUESTEL-ORBIT - image

PN - US6349670 B1 20020226 [US6349670]

(B1) Plasma treatment equipment TI

(B1) ALPS ELECTRIC CO LTD (JP) PA

Alps Electric Company, Ltd., Tokyo [JP] PA0

(B1) FUKUDA KOICHI (JP); KIM SUNG CHUL (JP); OHMI TADAHIRO IN

(JP); ONO SHOICHI (JP); KASAMA YASUHIKO (JP); NAKANO AKIRA

(JP)

US44253999 19991118 [1999US-0442539] AP

JP34080698 19981130 [1998JP-0340806] PR

(B1) C23C-016/00 IC H01J-037/32H1

EC

ORIGINAL (O): 118723000E; CROSS-REFERENCE (X): 156345470 **PCL**

Corresponding document DT

US5472561; US5942039; US6051100 CT

(B1) U.S. Patent (no pre-grant pub.) after Jan. 2, 2001 STG

The invention provides a plasma equipment which is advantageous in that the AB suscepter impedance is small, the dependence on the frequency is low, the power consumption efficiency is high, the film forming speed is faster as compared with conventional plasma equipment, and the film quality is high. Metal plates AC short between a chamber wall and a shield of an electrode of the same DC potential as the chamber.

2002-10 UP

1/1 LGST - ©EPO

- US6349670 B1 20020226 [US6349670] PN

US44253999 19991118 [1999US-0442539] AP

ACT -19991118 US/AS-A

ASSIGNMENT

OWNER: ALPS ELECTRIC CO., LTD. 1-7 YUKIGAYA, OTSUKA-CHO O;

EFFECTIVE DATE: 19991108

ASSIGNMENT OF ASSIGNORS INTEREST; ASSIGNORS: NAKANO,

AKIRA;KIM, SUNG CHUL;FUKUDA, KOICHI;AND

OTHERS;REEL/FRAME:010399/0481

20020924 US/CC-A

CERTIFICATE OF CORRECTION

20040519 US/AS-A

ASSIGNMENT

OWNER: ALPS ELECTRIC CO., LTD. 1-7 YUKIGAYA, OTSUKA-CHOOT;

EFFECTIVE DATE: 19991108

CORRECTIVE ASSIGNMENT; ASSIGNORS: NAKANO,

AKIRA /AR;REEL/FRAME:014635/0321

20040601 US/RF-A

REISSUE APPLICATION FILED

EFFECTIVE DATE: 20040225

UP - 2005-23

1/1 CRXX - @CLAIMS/RRX

PN - 6,349,670 A 20020226 [US6349670]

PA - Alps Electric Co Ltd JP

ACT - 20040225 REISSUE REQUESTED ISSUE DATE OF O.G.: 20040601

REISSUE REQUEST NUMBER: 10/786914

EXAMINATION GROUP RESPONSIBLE FOR REISSUEPROCESS: 1763

Reissue Patent Number:

20040519 REASSIGNED CORRECTIVE ASSIGNMENT

Assignor: NAKANO, AKIRA, DATE SIGNED: 11/08/1999 KIM, SUNG CHUL, DATE SIGNED: 11/08/1999 FUKADA, KOICHI, DATE SIGNED: 11/08/1999 KASAMA, YASUHIKO, DATE SIGNED: 11/08/1999 OHMI, TADAHIRO, DATE SIGNED: 11/08/1999 ONO, SHOICHI, DATE SIGNED: 11/08/1999

Assignee: ALPS ELECTRIC CO., LTD., 1-7 YUKIGAYA, OTSUKA-CHO, OTA-KU, TOKYO, JAPAN OHMI, TADAHIRO, 2-1-17 KOMEGAFUKURO, AOBA-KU, SENDAI-SHI, MIYAGI-KEN, JAPAN

Reel 014635/Frame 0321

Contact: ANTHONY P. CURTIS, PH.D., P.O. BOX 10395, CHICAGO, IL 60610

Search statement 2

Query/Command: FILE INPADOC

LGST - Time in minutes : 0,02 The cost estimation below is based on Questel's

standard price list

Estimated cost : 0.02 USD

Records displayed and billed : 1

Estimated cost: 0.65 USD

Cost estimated for the last database search : 0.67 USD Estimated total session cost : 1.28 USD

- Time in minutes : 0,02 The cost estimation below is based on Questel's standard price list Estimated cost: 0.03 USD Records displayed and billed : Estimated cost : Cost estimated for the last database search : Estimated cost : 5.70 USD 5.73 USD 7.01 USD Estimated total session cost - Time in minutes: 0,01 The cost estimation below is based on Questel's standard price list 0.02 USD Estimated cost : Cost estimated for the last database search : 0.02 USD 7.03 USD Estimated total session cost PLUSPAT - Time in minutes : 0,24 The cost estimation below is based on Questel's standard price list 0.66 USD Estimated cost : Records displayed and billed : 1 1.40 USD Estimated cost : Cost estimated for the last database search: 2.06 USD 9.09 USD Estimated total session cost Selected file: INPADOC You are now connected to INPADOC Covers 1968/1973 thru weekly updates (2005-49) For information on content, (..) INFO INPD.

Query/Command: FAM US6349670/PN

1 Patent Groups

Search statement

** SS 1: Results 12

Search statement 2

Query/Command: FAMSTATE NONSTOP

1/12 INPADOC - ©INPADOC

PN - DE 69924767 C0 20050519 [DE69924767]

TI - Plasmabearbeitungsgert und Werkzeug zur Impedanzmessung

IN - NAKANO AKIRA [JP]; KIM CHUL [KR]; FUKUDA KOICHI [JP]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - DE 69924767/99-A 19991125 [1999DE-6024767]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

2/12 INPADOC - ©INPADOC

PN - DE 69924767 T2 20050901 [DE69924767]

TI - Plasmabearbeitungsgert und Werkzeug zur Impedanzmessung

IN - NAKANO AKIRA [JP]; KIM CHUL [KR]; FUKUDA KOICHI [JP]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - DE 69924767/99-A 19991125 [1999DE-6024767]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

3/12 INPADOC - ©INPADOC

PN - EP 1030345 A2 20000823 [EP1030345]

TI - Plasma treatment equipment and impedance measurement tool
Appareil de traitement au plasma et dispositif de mesure d'impdance
Plasmabearbeitungsgert und Werkzeug zur Impedanzmessung

LA - ENG

IN - NAKANO AKIRA [JP]; KIM SUNG CHUL [KR]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]; FUKUDA KOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - EP 99309434/99-A 19991125 [1999EP-0309434]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32

DS - DE* FR* GB* IT* NL*

1/1 LEGALI - ©EPO

PN - EP1030345 A2 20000823 [EP1030345]EP1030345 A3 20030205 [EP1030345] EP1030345 B1 20051019 [EP1030345]

AP - EP99309434 19991125 [1999EP-0309434]

ACTE - 20000823 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20000823 EP/AX-A [+] EXTENSION OF THE EUROPEAN PATENT TO

AL;LT;LV;MK;RO;SI

20020717 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED

EFFECTIVE DATE: 20020516

20020821 EP/R17P-A [+]

REQUEST FOR EXAMINATION FILED (CORRECTION) EFFECTIVE DATE: 20020521

20030205 EP/AK-A [+]
DESIGNATED CONTRACTING STATES:
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20030205 EP/AX-A [+] EXTENSION OF THE EUROPEAN PATENT TO AL LT LV MK RO SI

20030205 EP/RIC1-A CLASSIFICATION (CORRECTION) 7 H01J-037/32 A

20030205 EP/RIC1-A CLASSIFICATION (CORRECTION) 7 G01R-027/22 B

20030618 EP/17Q-A [+] FIRST EXAMINATION REPORT EFFECTIVE DATE: 20030506

20031022 EP/AKX-A [+] PAYMENT OF DESIGNATION FEES DE FR GB IT NL

20051019 EP/AK-A [+]
DESIGNATED CONTRACTING STATES:
DE FR GB IT NL

20051019 EP/REG-A; GB/FG4D [+] GB: EUROPEAN PATENT GRANTED <GB>

UP - 2005-43

4/12 INPADOC - @INPADOC

PN - EP 1030345 A3 20030205 [EP1030345]

TI - PLASMA TREATMENT EQUIPMENT AND IMPEDANCE MEASUREMENT TOOL

LA - ENG

IN - NAKANO AKIRA [JP]; KIM SUNG CHUL [KR]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]; FUKUDA KOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - EP 99309434/99-A 19991125 [1999EP-0309434]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

DS - AT* BE* CH* CY* DE* DK* ES* FI* FR* GB* GR* IE* IT* LI* LU* MC*

NL* PT* SE*

1/1 LEGALI - ©EPO

PN - EP1030345 A2 20000823 [EP1030345]EP1030345 A3 20030205 [EP1030345]

EP1030345 B1 20051019 [EP1030345]

AP - EP99309434 19991125 [1999EP-0309434]

ACTE -

20000823 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20000823 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

AL;LT;LV;MK;RO;SI

20020717 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED

EFFECTIVE DATE: 20020516

20020821 EP/R17P-A [+]

REQUEST FOR EXAMINATION FILED (CORRECTION)

EFFECTIVE DATE: 20020521

20030205 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20030205 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

AL LT LV MK RO SI

20030205 EP/RIC1-A

CLASSIFICATION (CORRECTION)

7 H01J-037/32 A

20030205 EP/RIC1-A

CLASSIFICATION (CORRECTION)

7 G01R-027/22 B

20030618 EP/17Q-A [+]

FIRST EXAMINATION REPORT

EFFECTIVE DATE: 20030506

20031022 EP/AKX-A [+]

PAYMENT OF DESIGNATION FEES

DE FR GB IT NL

20051019 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

DE FR GB IT NL

20051019 EP/REG-A; GB/FG4D [+] GB: EUROPEAN PATENT GRANTED <GB>

UP - 2005-43

5/12 INPADOC - @INPADOC

PN - EP 1406292 A2 20040407 [EP1406292]

TI - Plasma treatment equipment and impedance measurement tool
Appareil de traitement au plasma et dispositif de mesure d'impdance
Plasmabearbeitungsgert und Werkzeug zur Impedanzmessung

LA - ENG

IN - NAKANO AKIRA [JP]; KIM SUNG CHUL [KR]; FUKUDA KOICHI [JP]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - EP 03023423/03-A 19991125 [2003EP-0023423]

PR - EP 99309434/99-A3 19991125 [1999EP-0309434] JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

DS - DE* FR* GB* IT* NL*

1/1 LEGALI - ©EPO

PN - EP1406292 A2 20040407 [EP1406292]EP1406292 A3 20040609 [EP1406292] EP1406292 B1 20050413 [EP1406292]

AP - EP03023423 19991125 [2003EP-0023423]

ACTE - 20040407 EP/AC-A

DIVISIONAL APPLICATION (ART. 76) OF:

(EP 1030345 0 [EP1030345])

20040407 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20040407 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

AL LT LV MK

20040407 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED

EFFECTIVE DATE: 20031017

20040609 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20040609 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO AL LT LV MK

20050302 EP/AKX-A
PAYMENT OF DESIGNATION FEES
DE FR GB IT NL

20050413 EP/AC-A DIVISIONAL APPLICATION (ART. 76) OF: (EP 1030345 0 [EP1030345])

20050413 EP/AK-A
DESIGNATED CONTRACTING STATES:
DE FR GB IT NL

20050413 EP/REG-A; GB/FG4D [+] GB: EUROPEAN PATENT GRANTED <GB>

20050518 EP/REG-A; IE/FG4D [+] IE: EUROPEAN PATENTS GRANTED DESIGNATING IRELAND <IE>

20050519 EP/REF-A CORRESPONDS TO: (DE 69924767 20050519 [DE69924767])

UP - 2005-26

6/12 INPADOC - @INPADOC

PN - EP 1406292 A3 20040609 [EP1406292]

TI - Plasma treatment equipment and impedance measurement tool
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AP - EP 03023423/03-A 19991125 [2003EP-0023423]

PR - EP 99309434/99-A3 19991125 [1999EP-0309434] JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

DS - AT* BE* CH* CY* DE* DK* ES* FI* FR* GB* GR* IE* IT* LI* LU* MC* NL* PT* SE*

1/1 LEGALI - ©EPO

PN

EP1406292 A2 20040407 [EP1406292]EP1406292 A3 20040609 [EP1406292]

EP1406292 B1 20050413 [EP1406292]

AP - EP03023423 19991125 [2003EP-0023423]

ACTE - 20040407 EP/AC-A

DIVISIONAL APPLICATION (ART. 76) OF:

(EP 1030345 0 [EP1030345])

20040407 EP/AK-A [+]

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20050302 EP/AKX-A

PAYMENT OF DESIGNATION FEES

DE FR GB IT NL

20050413 EP/AC-A

DIVISIONAL APPLICATION (ART. 76) OF:

(EP 1030345 0 [EP1030345])

20050413 EP/AK-A

DESIGNATED CONTRACTING STATES:

DE FR GB IT NL

20050413 EP/REG-A; GB/FG4D [+]

GB: EUROPEAN PATENT GRANTED

<GB>

20050518 EP/REG-A; IE/FG4D [+]

IE: EUROPEAN PATENTS GRANTED DESIGNATING IRELAND

<IE>

20050519 EP/REF-A

CORRESPONDS TO:

(DE 69924767 20050519 [DE69924767])

UP - 2005-26

7/12 INPADOC - @INPADOC

PN - EP 1406292 B1 20050413 [EP1406292]

TI - Plasma treatment equipment and impedance measurement tool
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LA - ENG

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PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - EP 03023423/03-A 19991125 [2003EP-0023423]

PR - EP 99309434/99-A3 19991125 [1999EP-0309434] JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

DS - DE* FR* GB* IT* NL*

1/1 LEGALI - ©EPO

PN - EP1406292 A2 20040407 [EP1406292]EP1406292 A3 20040609 [EP1406292] EP1406292 B1 20050413 [EP1406292]

AP - EP03023423 19991125 [2003EP-0023423]

ACTE - 20040407 EP/AC-A

DIVISIONAL APPLICATION (ART. 76) OF:

(EP 1030345 0 [EP1030345])

20040407 EP/AK-A [+]

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AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20040407 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

AL LT LV MK

20040407 EP/17P-A [+]

REQUEST FOR EXAMINATION FILED

EFFECTIVE DATE: 20031017

20040609 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20040609 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

AL LT LV MK

20050302 EP/AKX-A

PAYMENT OF DESIGNATION FEES

DE FR GB IT NL

20050413 EP/AC-A DIVISIONAL APPLICATION (ART. 76) OF: (EP 1030345 0 [EP1030345])

20050413 EP/AK-A
DESIGNATED CONTRACTING STATES:
DE FR GB IT NL

20050413 EP/REG-A; GB/FG4D [+] GB: EUROPEAN PATENT GRANTED <GB>

20050518 EP/REG-A; IE/FG4D [+]
IE: EUROPEAN PATENTS GRANTED DESIGNATING IRELAND
<IE>

20050519 EP/REF-A CORRESPONDS TO: (DE 69924767 20050519 [DE69924767])

UP - 2005-26

8/12 INPADOC - @INPADOC

PN - EP 1030345 B1 20051019 [EP1030345]

TI - Plasma treatment equipment and impedance measurement tool
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Plasmabearbeitungsgert und Werkzeug zur Impedanzmessung

LA - ENG

IN - NAKANO AKIRA [JP]; KIM SUNG CHUL [KR]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]; FUKUDA KOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]; OHMI TADAHIRO [JP]

AP - EP 99309434/99-A 19991125 [1999EP-0309434]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

IC - H01J-037/32; G01R-027/22

DS - DE* FR* GB* IT* NL*

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PN - EP1030345 A2 20000823 [EP1030345]EP1030345 A3 20030205 [EP1030345] EP1030345 B1 20051019 [EP1030345]

AP - EP99309434 19991125 [1999EP-0309434]

ACTE - 20000823 EP/AK-A [+]

DESIGNATED CONTRACTING STATES:

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20000823 EP/AX-A [+]

EXTENSION OF THE EUROPEAN PATENT TO

AL;LT;LV;MK;RO;SI

20020717 EP/17P-A [+] REQUEST FOR EXAMINATION FILED EFFECTIVE DATE: 20020516

20020821 EP/R17P-A [+]
REQUEST FOR EXAMINATION FILED (CORRECTION)
EFFECTIVE DATE: 20020521

20030205 EP/AK-A [+]
DESIGNATED CONTRACTING STATES:
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

20030205 EP/AX-A [+] EXTENSION OF THE EUROPEAN PATENT TO AL LT LV MK RO SI

20030205 EP/RIC1-A CLASSIFICATION (CORRECTION) 7 H01J-037/32 A

20030205 EP/RIC1-A CLASSIFICATION (CORRECTION) 7 G01R-027/22 B

20030618 EP/17Q-A [+] FIRST EXAMINATION REPORT EFFECTIVE DATE: 20030506

20031022 EP/AKX-A [+] PAYMENT OF DESIGNATION FEES DE FR GB IT NL

20051019 EP/AK-A [+]
DESIGNATED CONTRACTING STATES:
DE FR GB IT NL

20051019 EP/REG-A; GB/FG4D [+] GB: EUROPEAN PATENT GRANTED <GB>

UP - 2005-43

9/12 INPADOC - ©INPADOC

PN - JP 2002189042 A2 20020705 [JP2002189042]

TI - IMPEDANCE-MEASURING INSTRUMENT

IN - NAKANO AKIRA; FUKUDA KOICHI; KIN SEITETSU; KASAMA YASUHIKO; OMI TADAHIRO; ONO SHOICHI

PA - ALPS ELECTRIC CO LTD; OMI TADAHIRO

AP - JP 2001280772/01-A 20010914 [2001JP-0280772]

PR - JP 2001280772/01-A 20010914 [2001JP-0280772]

JP 345852/97-A 19971130 [1997JP-0345852]

IC - G01R-027/02; G01R-001/067; H05H-001/00

10/12 INPADOC - @INPADOC

PN - JP 3705582 B2 20051012 [JP3705582]

АР - JP 2001280772/01-A 20010914 [2001JP-0280772]

PR - JP 2001280772/01-A 20010914 [2001JP-0280772]

JP 345852/97-A 19971130 [1997JP-0345852]

IC - G01R-027/02; G01R-001/067; H05H-001/00

11/12 INPADOC - @INPADOC

PN - JP 11251094 A2 19990917 [JP11251094]

TI - PLASMA PROCESSING DEVICE AND IMPEDANCE MEASURING TOOL

IN - NAKANO AKIRA; FUKUDA KOICHI; KIN SEITETSU; KASAMA YASUHIKO; OMI TADAHIRO; ONO SHOICHI

PA - FRON TEC KK; ALPS ELECTRIC CO LTD; OMI TADAHIRO

AP - JP 340806/98-A 19981130 [1998JP-0340806]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

JP 345852/97-A 19971130 [1997JP-0345852]

IC - H05H-001/46; C23C-016/50; H01L-021/205; H01L-021/3065

12/12 INPADOC - @INPADOC

PN - US 6349670 BA 20020226 [US6349670]

TI - PLASMA TREATMENT EQUIPMENT

IN - NAKANO AKIRA [JP]; FUKUDA KOICHI [JP]; KIM SUNG CHUL [JP]; KASAMA YASUHIKO [JP]; OHMI TADAHIRO [JP]; ONO SHOICHI [JP]

PA - ALPS ELECTRIC CO LTD [JP]

AP - US 442539/99-A 19991118 [1999US-0442539]

PR - JP 340806/98-A 19981130 [1998JP-0340806]

IC - C23C-016/00

1/1 LEGALI - ©EPO

PN - US6349670 B1 20020226 [US6349670]

AP - US44253999 19991118 [1999US-0442539]

ACTE - 19991118 US/AS-A

ASSIGNMENT

OWNER: ALPS ELECTRIC CO., LTD. 1-7 YUKIGAYA, OTSUKA-CHO O;

EFFECTIVE DATE: 19991108

ASSIGNMENT OF ASSIGNORS INTEREST; ASSIGNORS: NAKANO,

AKIRA;KIM, SUNG CHUL;FUKUDA, KOICHI;AND

OTHERS;REEL/FRAME:010399/0481

20020924 US/CC-A CERTIFICATE OF CORRECTION

20040519 US/AS-A
ASSIGNMENT
OWNER: ALPS ELECTRIC CO., LTD. 1-7 YUKIGAYA, OTSUKA-CHOOT;
EFFECTIVE DATE: 19991108
CORRECTIVE ASSIGNMENT; ASSIGNORS: NAKANO,
AKIRA /AR; REEL/FRAME: 014635/0321

20040601 US/RF-A REISSUE APPLICATION FILED EFFECTIVE DATE: 20040225

UP - 2005-23

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